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Notice of Allowability	Application No.	Applicant(s)
	10/813,317	SCHWAN, CHRISTOPH
	Examiner	Art Unit
	Michael Trinh	2822
The MAILING DATE of this communication apper All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication GHTS. This application is subject to	lication. If not included will be mailed in due course. THIS
1. This communication is responsive to <u>12/27/05</u> .		·
2. $\boxtimes$ The allowed claim(s) is/are $\underline{1,3-13,15-26,28-31}$ and $\underline{33-36}$ .		
<ul> <li>3.  Acknowledgment is made of a claim for foreign priority unally All b)  Some* c) None of the:</li> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> </ul>	been received.	
3. Copies of the certified copies of the priority documents have been received in this national stage application from the		
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		·
Applicant has THREE MONTHS FROM THE "MAILING DATE" on noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  4. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give	ENT of this application.  itted. Note the attached EXAMINER's	S AMENDMENT or NOTICE OF
5. CORRECTED DRAWINGS (as "replacement sheets") mus		ion is delicient.
(a) ☐ including changes required by the Notice of Draftspers	•	)10) attacked
1) hereto or 2) to Paper No./Mail Date		946) attached
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	Amendment / Comment or in the O	
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	ne header according to 37 CFR 1.121(d	).
6. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT F	sit of BIOLOGICAL MATERIAL m FOR THE DEPOSIT OF BIOLOGICA	ust be submitted. Note the LL MATERIAL.
Attachment(s)	_	•
1. Notice of References Cited (PTO-892)	<u> </u>	atent Application (PTO-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6.  ☐ Interview Summary ( Paper No./Mail Date	PTO-413),
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/08         Paper No./Mail Date     </li> </ol>	8), 7. ☐ Examiner's Amendm	ent/Comment
<ol> <li>Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ol>	8. ⊠ Examiner's Statemer 9. □ Other	Michael Trimin Primary Examiner

Art Unit: 2822

## **DETAILED ACTION**

\*\*\* This office action is in response to Applicant's Amendment filed December 17, 2005. Claims 1,3-13,15-26,28-31,33-36 are pending.

## Allowable Subject Matter

- 1. Claims 1,3-13,15-26,28-31,33-36 are allowed.
- 2. The following is a statement of reasons for the indication of allowable subject matter:

Applicant's amendment and convincing remarks filed December 27, 2005 have overcome the rejections of record, in which the references including Bae et al (2002/0182795), Lin (6,534,388), etc., of record, alone or in combination, do not fairly anticipatively disclose each and every aspect of the claimed method for forming spacer elements, or fairly make a prima facie obvious case of the claimed method, in combination with other processing claimed limitations as recited in base claim, among other limitations, the inclusion of, such as in claim 21, forming a sacrificial spacer at least from a second spacer layer of a spacer layer stack comprising a first etch stop layer formed of a first material, a first spacer layer formed of a second material, a second etch stop layer formed of the first material and a second spacer layer formed of the second material; and forming spacer elements at least from the first spacer layer by removing the sacrificial spacer, wherein the steps of forming sacrificial sidewall spacers and forming the conformal spacer elements by removing the sacrificial sidewall spacers are performed in a single etch chamber as an *in-situ* etch process.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael M. Trinh whose telephone number is (571) 272-1847. The examiner can normally be reached on M-F: 9:00 Am to 5:30 Pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra Smith can be reached on (571) 272-2429. The central fax phone number is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free)

Michael Trinh
Primary Examinor